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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Michael L. McSwiney et al.

Serial No.: 10/764,193

Filed: January 23, 2004

For: Forming a Silicon  
Nitride Film

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Art Unit: 1762

Examiner: Renee R. Berry

Atty Docket: ITL.1056US  
P17793

Assignee: Intel Corporation

Mail Stop **Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO RESTRICTION REQUIREMENT**

Sir:

In response to the restriction requirement mailed July 2, 2007, please amend the above-referenced patent application as follows:

Date of Deposit: July 13, 2007

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

*Cynthia L. Hayden*  
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